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IN THE SPECIFICATION

Please amend the portions of the Specification identified below to read as indicated herein.

Paragraph beginning at page 13, line1:

The illumination system in the present embodiment example contains, as the light source 1, a pinch plasma source; as the EUV collector, a collector mirror- $\frac{3}{3}$ that collects the light and reflects it onto field raster element plate 7; a pupil raster element plate 10, and a reticle in a reticle plane 14. By reflection at the field raster elements 5, the light is guided to the individual pupil raster elements 9 of the pupil raster element plate 11 and from there it is guided into reticle plane 14. The pinch plasma source is an extensive light source (roughly 1 mm) with a directional radiation in a relatively small range of solid angles of approximately $\Omega = 0.3$ sr. The exit pupil of the illumination system is not shown in Figure 3.

Paragraph beginning at page 16, line4:

In reflective systems, field raster elements 5 can be mirror elements with collecting effect.

As an alternative to this, the collecting effect can be transferred entirely to the collector mirror 3A and the field raster elements can be configured as planar facets.

Paragraph beginning at page 18, line 10:

Figure 10 shows a complete EUV illumination system, in which a system according to the invention is shown for adjusting the illumination in an exit pupil 24 of an illumination system 26, which coincides with an entrance pupil 100 of an objective 102. The system comprises a light source 1, a collector mirror—3 3A for collecting the light of light source 1, a first optical element 4 with raster elements, a second optical element 8 with raster elements, and three field-forming mirrors 12.1, 12.2, 12.3, which are arranged after the second optical element 8 and which essentially serve to form a field in a reticle plane 14. A reticle in reticle plane 14 is a reflection

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mask in the present case. The reticle can move in the y-direction in the EUV system, designed as a scanning system.